Electronic supplementary information

for

Highly ordered TiO₂ nanostructures by sequential vapour infiltration of block copolymer micellar films in an atomic layer deposition reactor†

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**Figure S1.** FTIR spectra of PS$_{23k}$-$b$-P4VP$_{4.5k}$ films before (a) and after (b) exposure of TiCl$_4$ vapour in the ALD reactor.